



*Old title: 3D pixel devices; design, production and characterisation in test beams*

## Characterisation of Glasgow/CNM double-sided 3D sensors

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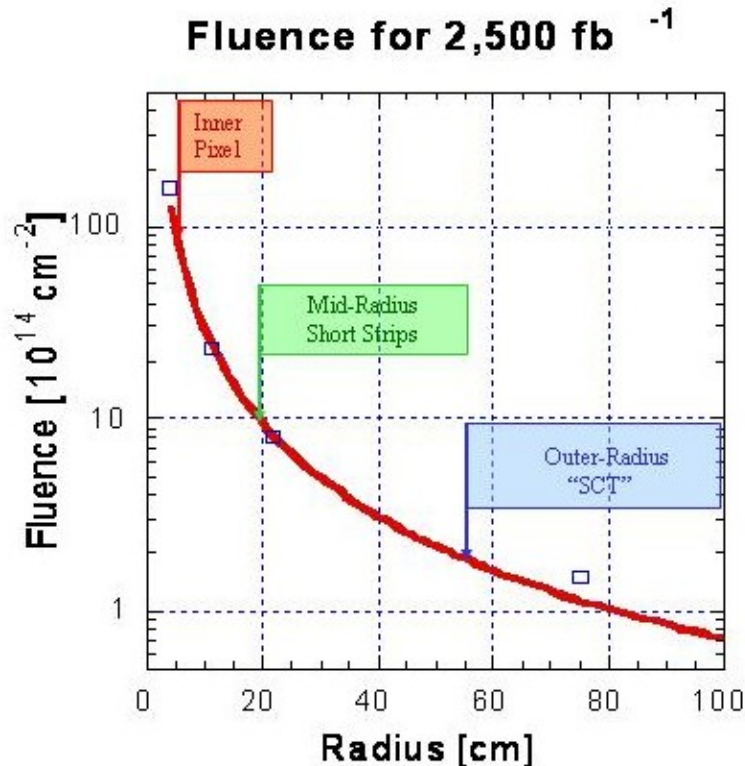
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# Motivation for radiation hard sensors

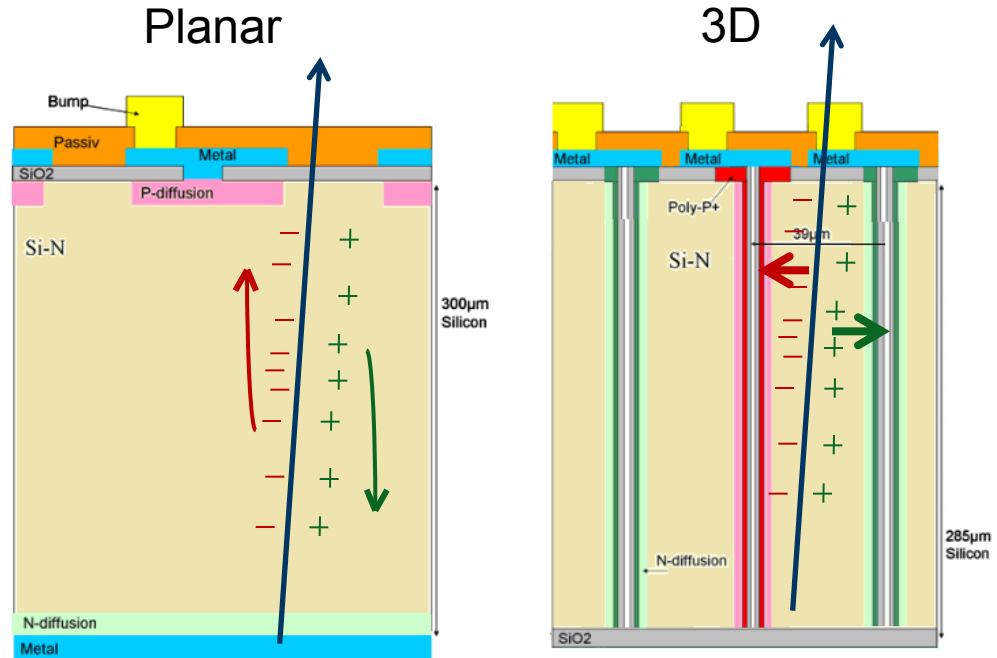


- Fact of 10 luminosity upgrade of LHC to HL-LHC to extend physics programme
- Radiation damage increase in proportion to integrated luminosity
- Need to optimise silicon detector design to survive

#203: *Silicon Detectors for High Luminosity Colliders. RD50 Status Report. Ulrich Parzefall*

- Radiation hardness requirements (including safety factor of 2)
  - $2 \times 10^{16} n_{eq}/cm^2$  for the innermost pixel layers
  - $1 \times 10^{15} n_{eq}/cm^2$  for the innermost strip layers

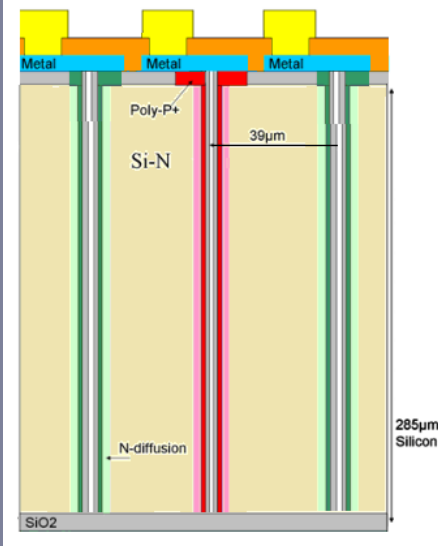
- **Greater signal charge** due to faster collection time (less trapping)
- **Reduced power consumption** due to lower depletion voltages
- **Reduced charge sharing**
- Active edge technology: large-area tiled 'edge-less' detectors



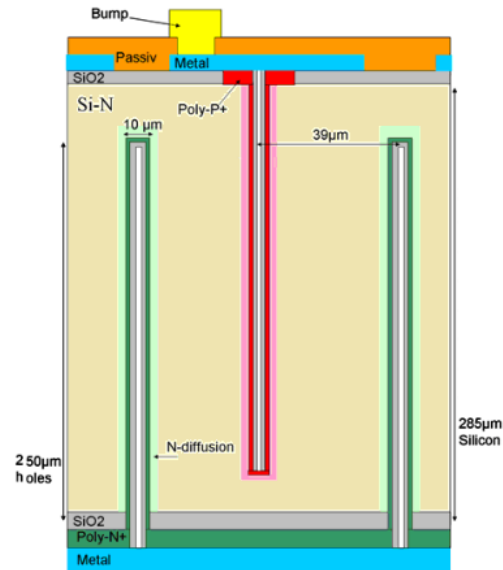
## Drawbacks

- increased complexity, **yield** issues
- areas of **inefficiency**

# Double sided 3D sensors



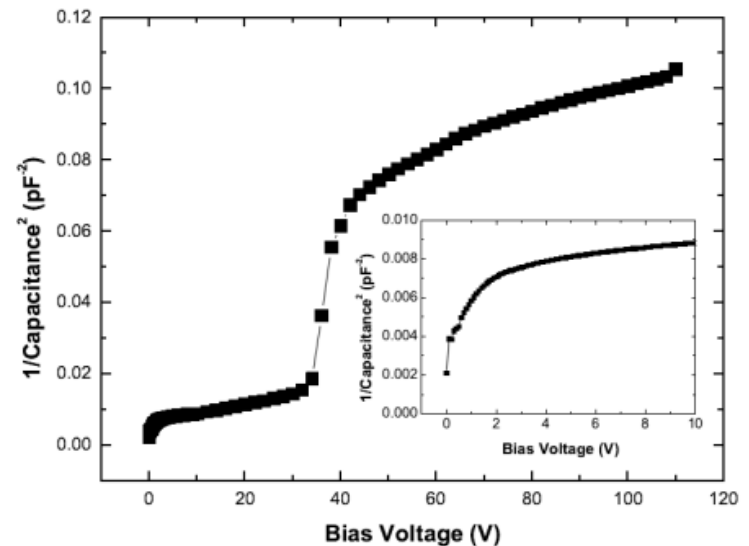
3D



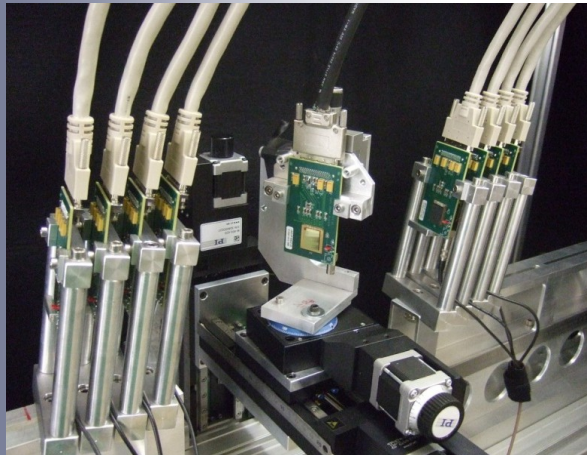
Double-sided 3D

Double depletion  
Lateral depletion ~4V  
Full depletion ~40V

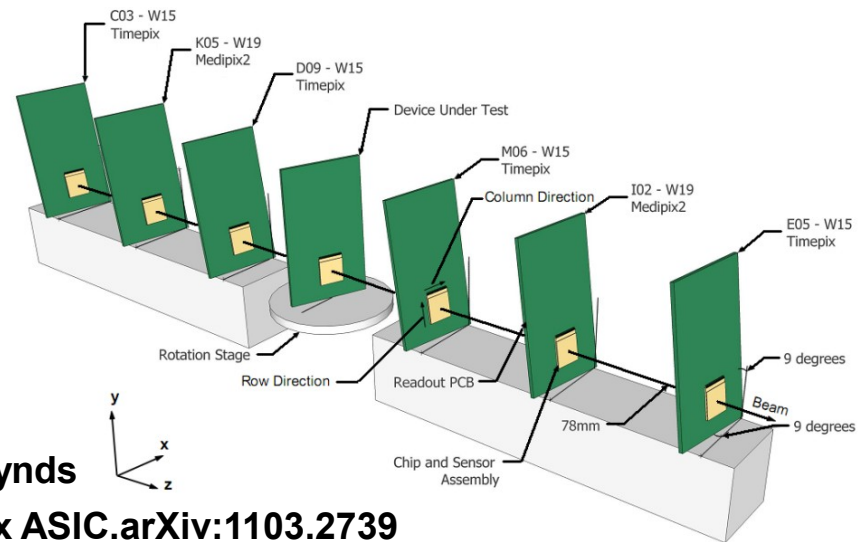
- Reduce fabrication complexity
- Increase yield
- All regions of sensor have active Silicon



## Timepix Telescope



- TimePix/Medipix chips: 256\*256 55 $\mu$ m square pixels
- Energy deposition provided by Time over Threshold in TimePix
- 120 GeV pion beam from SPS
- Device under test (DUT): double sided 3D N-type pixel sensor
- DUT on high resolution rotational and translational stage



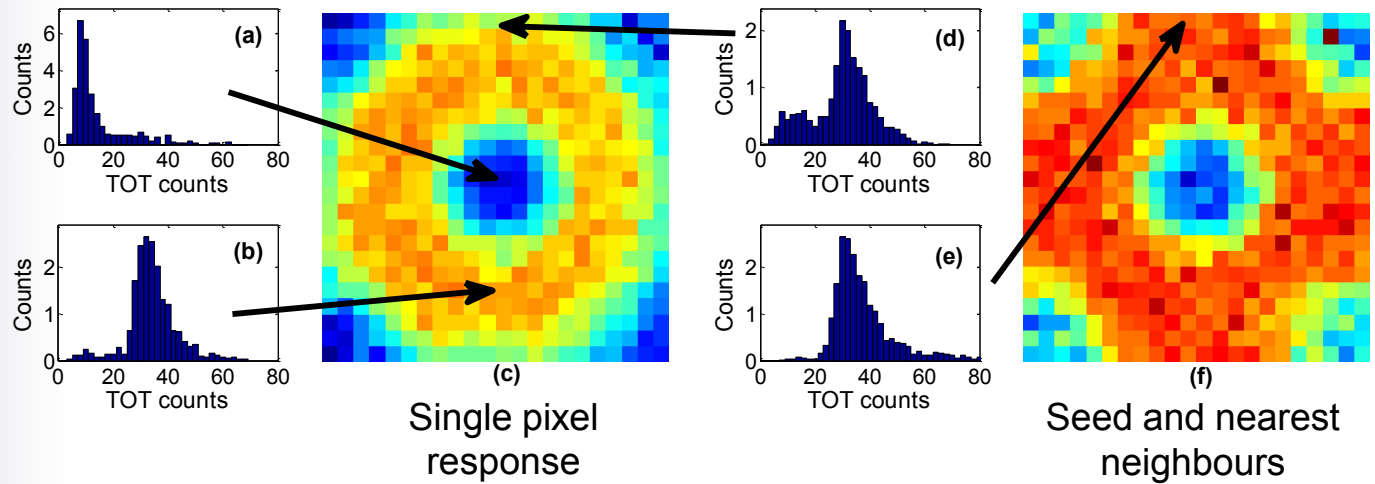
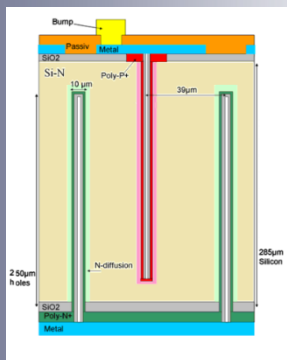
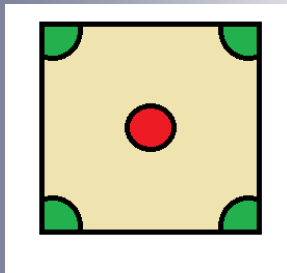
For more details on telescope see

- # 147 - The LHCb VELO upgrade. Daniel Hynds
- Charged Particle Tracking with the Timepix ASIC. arXiv:1103.2739



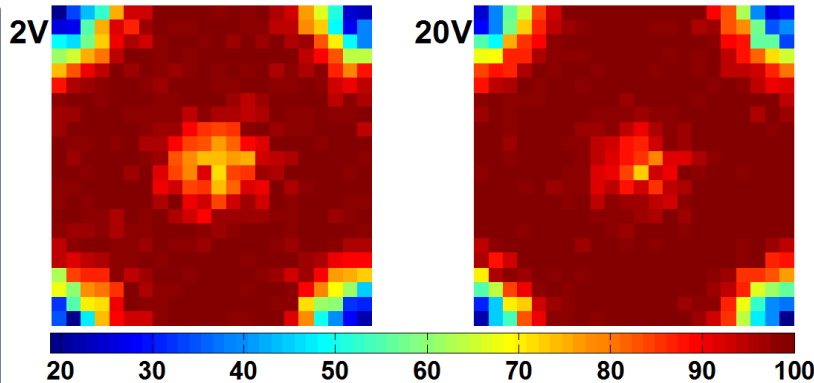
## Timepix Telescope

Mean energy deposited mapped onto pixel cell



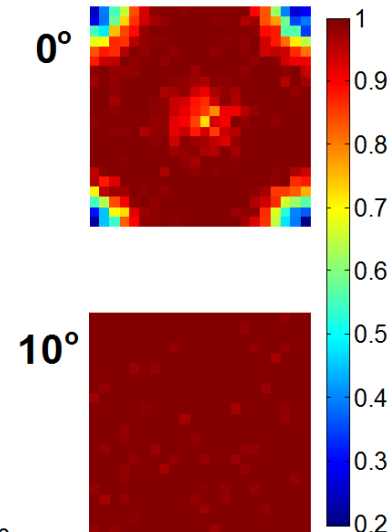
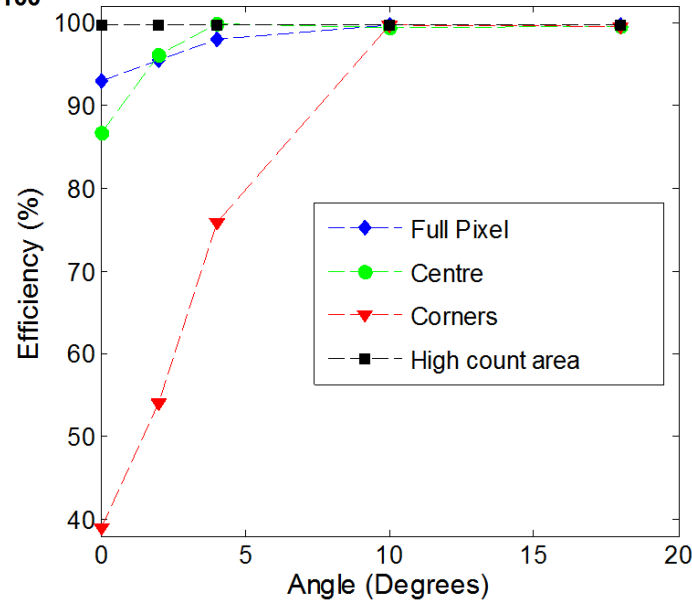
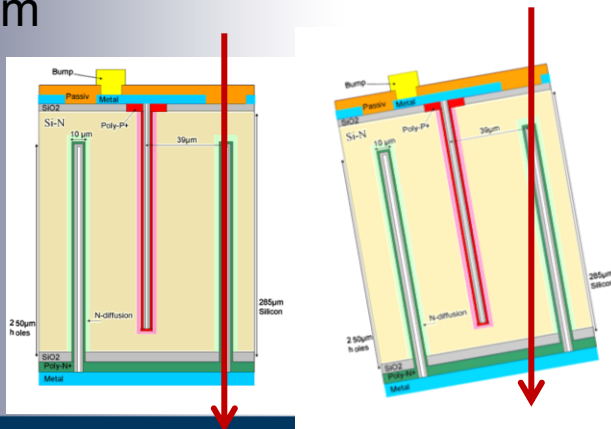
- Area removed from columns exhibits standard Landau shape
- Charge deposition full/column ratio =  $35/285\mu\text{m}$  ratio
- Full cluster energy reconstruction

## Timepix Telescope



Voltage	Corner	Centre	Ring	Pixel
2V	35.6	79.1	99.1	91.2
20V	39.1	86.7	99.7	93.0

Full efficiency,  $99.8 \pm 0.5\%$ , reached at an angle of  $10^\circ$  to the incident beam

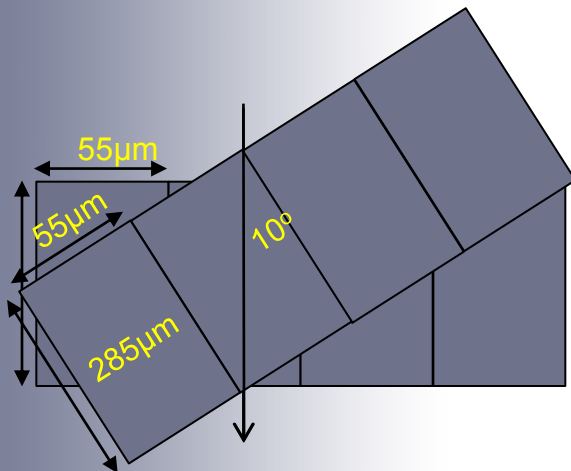


## Timepix Telescope

$$\text{Binary resolution} = 55\mu\text{m} / \sqrt{12} = 15.9\mu\text{m}$$

	3D		Planar *	
Degrees	0°	10°	0°	10°
Spatial resolution	15.8±0.1	9.18±0.1	10.15±0.1	5.86±0.1

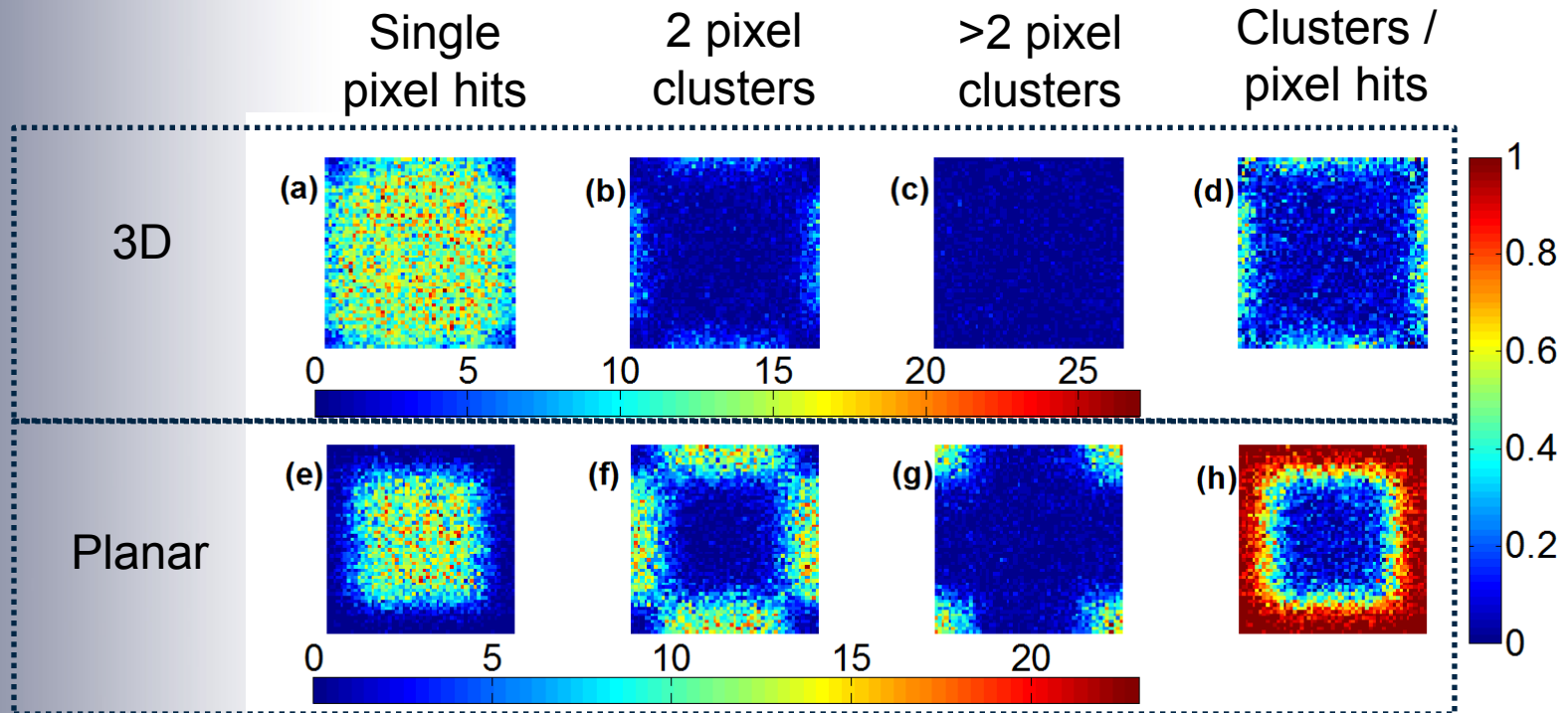
***Resolutions shown can be and have been improved with eta corrections and the removal of track extrapolation error***



- Hits that only affect one pixel have limited resolution
- Tilting the sensor means all tracks charge share
- Can use ToT information in centroid, CoG calculations
- Maximum spatial resolution at 10° \*



## Timepix Telescope

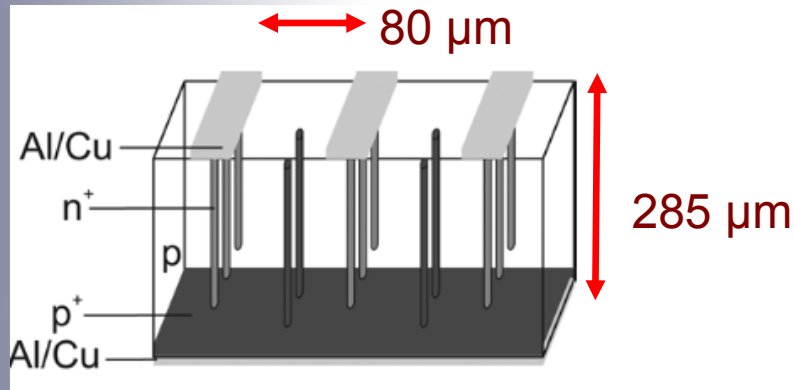


**59%** of incident particles multiple pixel hits in the **planar** sensor.

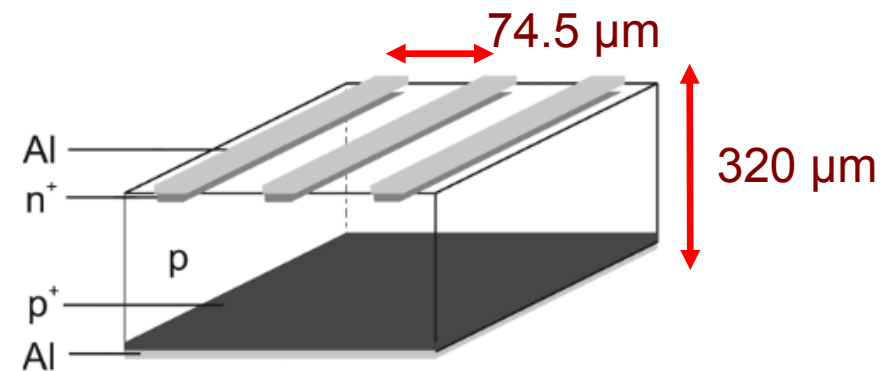
**14%** of incident particles multiple pixel hits in the **3D** sensor.

## Electrical measurements

### 3D



### Planar



0.5 1,2,5,10,20  $\times 10^{15}$  1 MeV  $n_{eq}$   $cm^{-2}$  ( $\pm 20\%$ )

Karlsruhe Institute of Technology,  $-20^{\circ}C$ , 26 MeV protons

### 3D devices

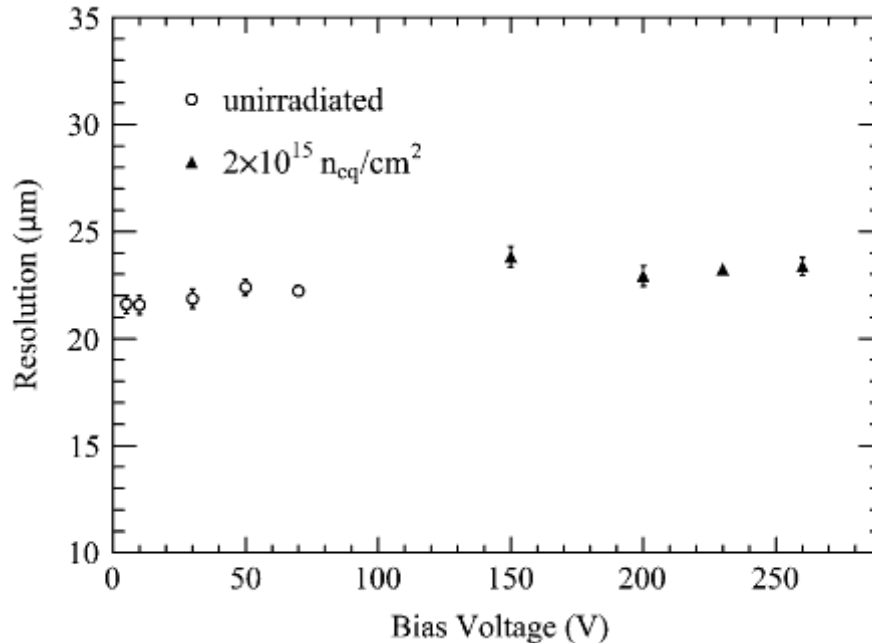
P-stop isolation before and after irradiation to  $10 \times 10^{15}$

Inter-strip resistance 100M $\Omega$

Leakage current scales as expected

Fluence ( $1 \times 10^{15}$ 1MeV $n_{eq}$ $cm^{-2}$ )	Lateral depletion voltage (V)
0	4
0.5	$15 \pm 5$
5	$100 \pm 10$
10	$145 \pm 10$

## Silicon Beam Telescope



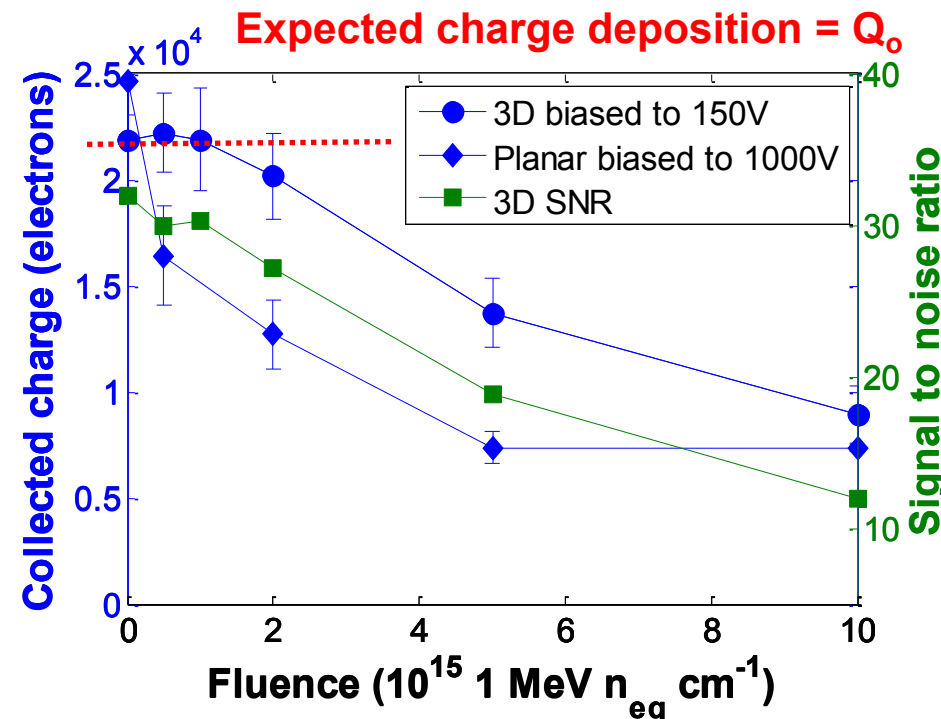
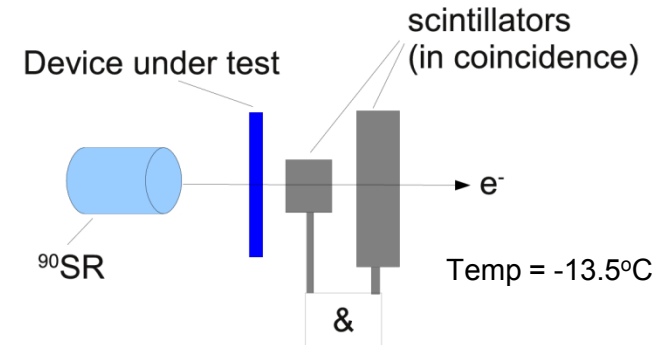
- Resolution before and after irradiation close to binary resolution
- Summer 2011 – highly irradiated sensors in TimePix Telescope

3D binary resolution =  $74.5\mu\text{m} / \sqrt{12} = 23.1\mu\text{m}$

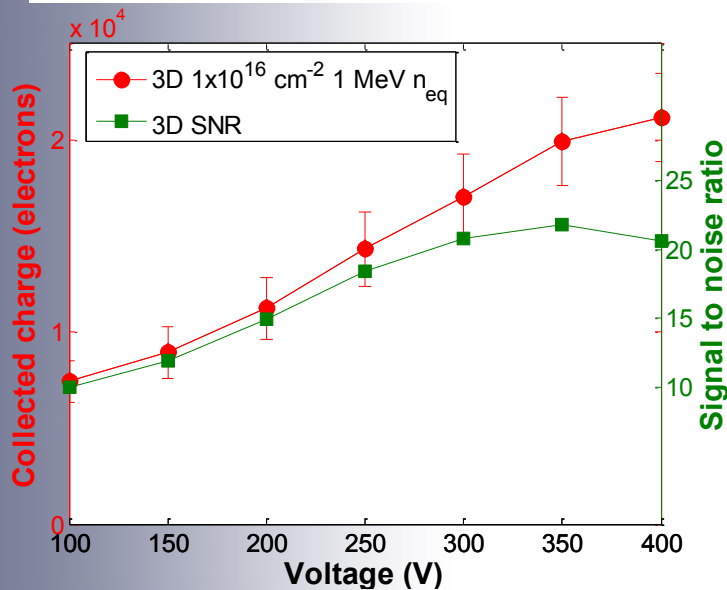
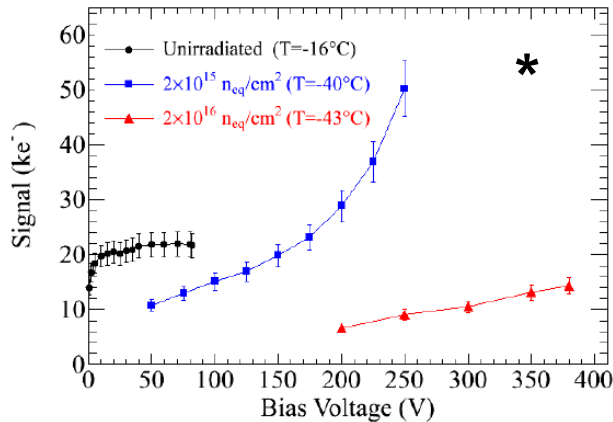
***The spatial resolutions contain telescope alignment error***

## Sr-90 electrons

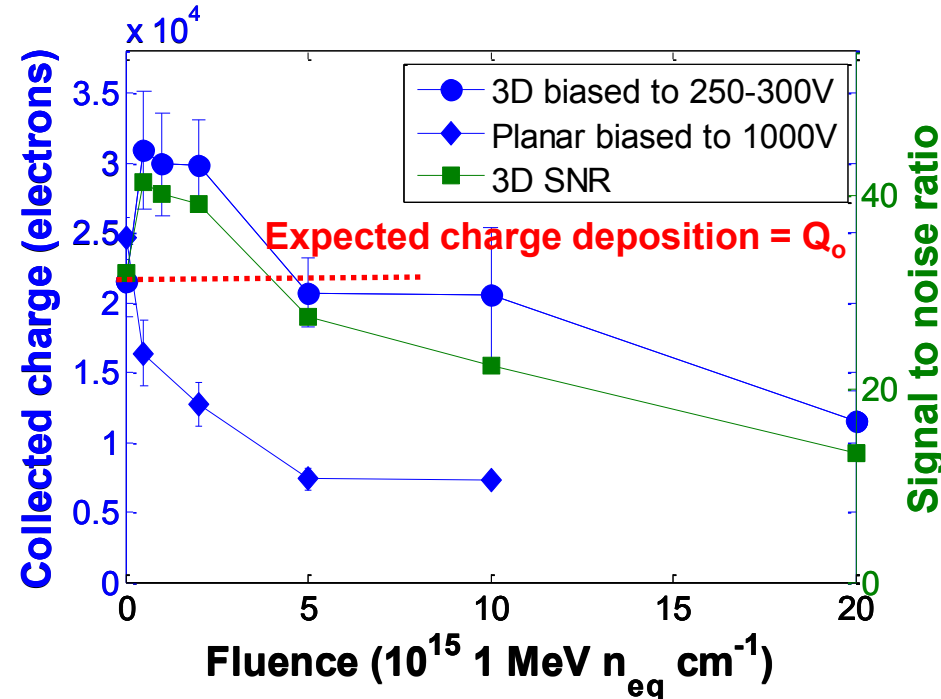
- Large charge collection at high fluences and modest voltages
- 3D charge collection of 47% of  $Q_0$  @  $10^{16}$  fluence at 150V
- This has been simulated using TCAD without any high field effects present and shows very good agreement
- Noise is constant giving a signal to noise value of  $>10$  @  $10^{16}$  fluence at 150V
- Compared to planar sensor higher charge collected
- Planar charge collection, 30% of  $Q_0$  @  $10^{16}$  fluence at 1000V



## Sr-90 electrons



## Charge multiplication through impact ionisation

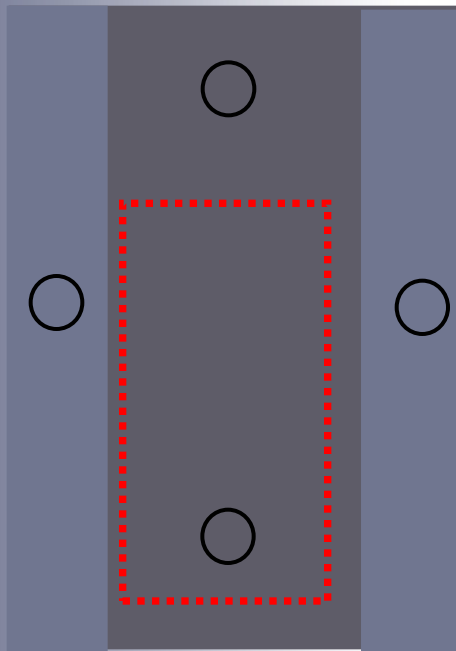
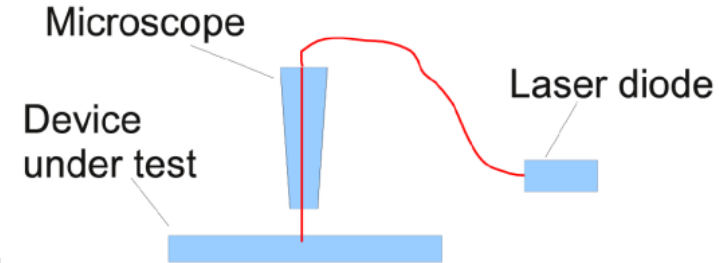


- 52% of  $Q_0$  collected at  $20 \times 10^{15} 1 \text{ MeV } n_{eq} \text{ cm}^{-1}$
- Charge Multiplication when bias  $> 150 \text{ V}$  ( $10^{15}$ )
- Noise  $\sim$  constant until  $> 250 \text{ V}$
- 3D Signal  $\gg$  Planar Signal (higher voltage)

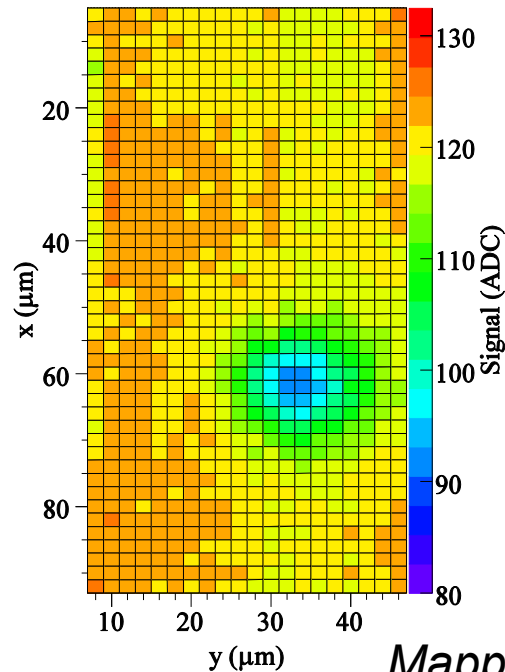
## Laser scanning

### Experimental setup:

- Space-resolved relative signal
- Motorised x-y stages, 4 $\mu\text{m}$  laser spot scanned in 2 $\mu\text{m}$  steps
- IR laser, 974 nm wavelength, absorption length:  $\sim 90\mu\text{m}$  (in Si,  $T=-20^\circ\text{C}$ )



Scanned area



Mapped charge collection response

- 3D un-irradiated @ 77V
- p+ column evident
- Uniform charge collection outside of column position



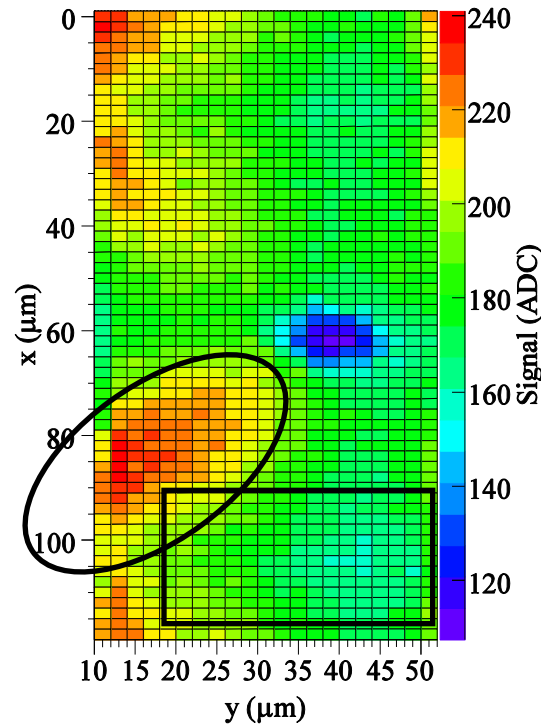
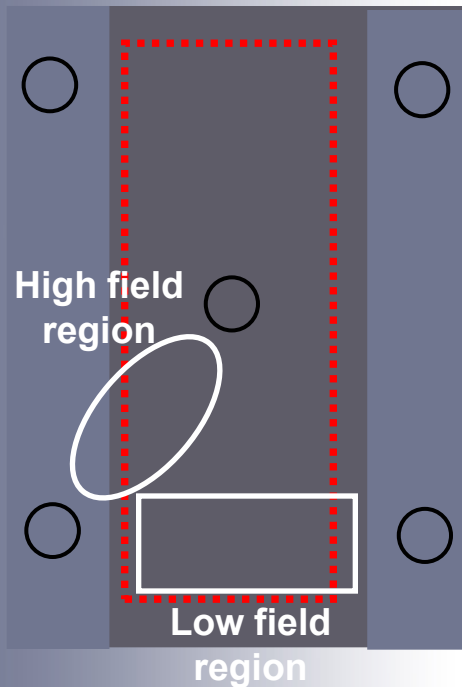
# Mapped CCE with scanned laser

## Laser scanning

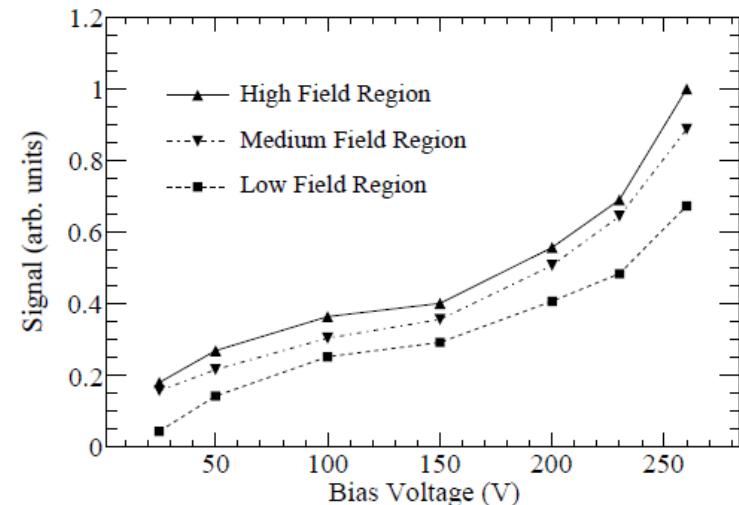
**Bias: 260V**

**Fluence:  $2 \times 10^{15}$  1 MeV  $n_{eq}$   $cm^{-2}$**

**Sr-90 measured  $\sim 137\%$  of  $Q_0$  collected**

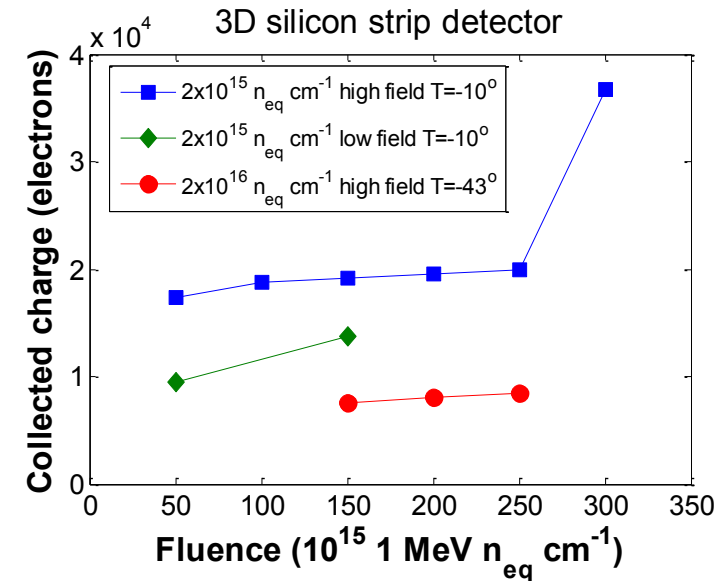
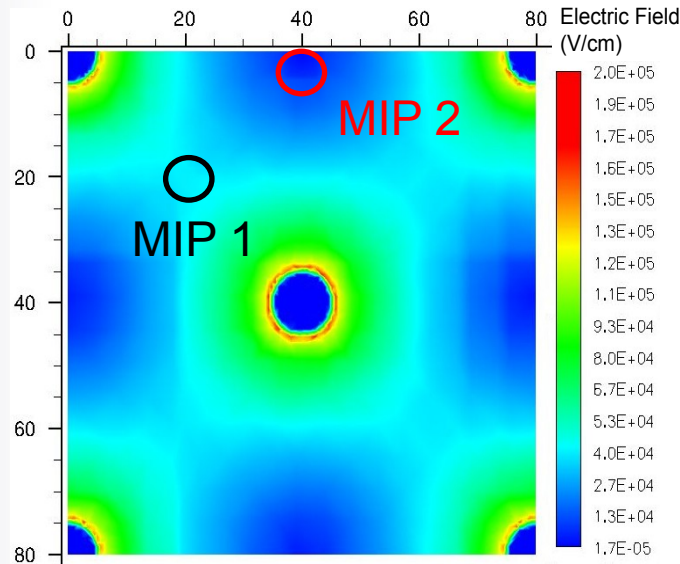
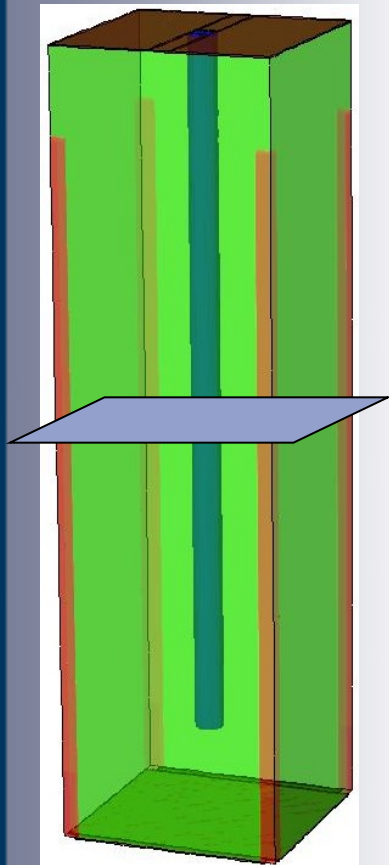


- p+ column evident
- Non-uniform charge collection outside of column position
- Area of low charge collection between the n+ contacts where a low field is present, greater probability of charge trapping



TCAD

$V_{\text{bias}} = 300 \text{ V}$  | Fluence =  $2 \cdot 10^{15} \text{ n/cm}^2$  |  $T = -10^\circ\text{C}$



- Charge multiplication occurs along column length
- Work on-going on low field region

Timepix Telescope

Electrical  
measurements

Sr-90 electrons

Laser scanning

TCAD

- Precision scans of the pixel performed, charge deposition mapped
  - Full charge collection from  $35\mu\text{m}$  active Si above column
- High efficiency across pixel matrix
  - $93.0\pm 0.5\%$  @  $0^\circ$ , **Full pixel efficiency,  $99.8\pm 0.5\%$** , at an angle of  $10^\circ$
- Large decrease in charge sharing compared to planar
  - MIPs that create clusters in sensor: 59% in planar, 14% in 3D
- Good electrical performance after irradiation
  - inter-strip resistance of  $100\text{M}\Omega$
- Higher collected charge at modest voltages for 3D
  - **47% of  $Q_0$  collected in 3D @150V, 30% in planar @1,000V**
- Charge multiplication in 3D irradiation device.
- Spatially resolved laser scanning uniform charge collection after irradiation
- Simulations can predict charge multiplication in irradiated devices

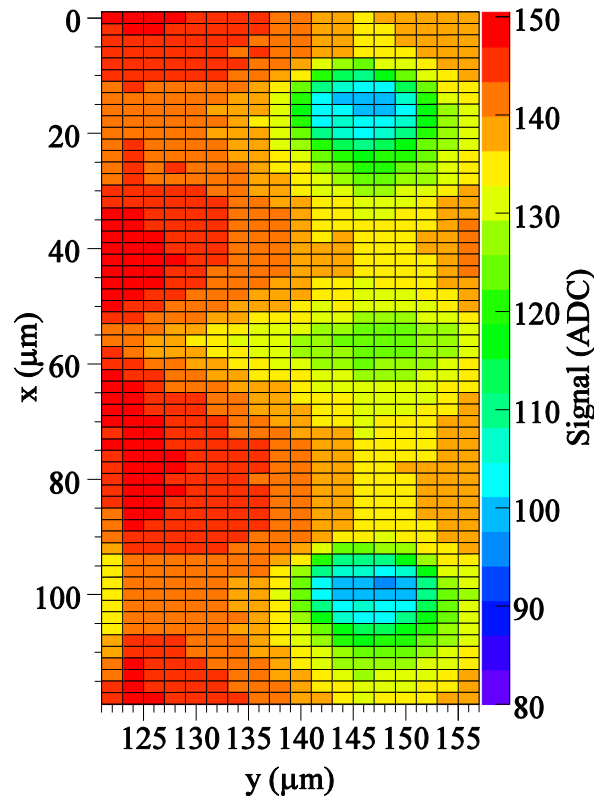
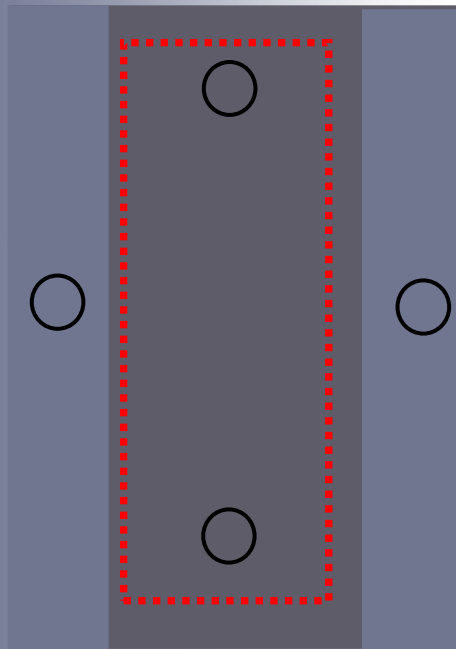
# Mapped CCE with scanned laser

## Laser scanning

**Bias: 150V**

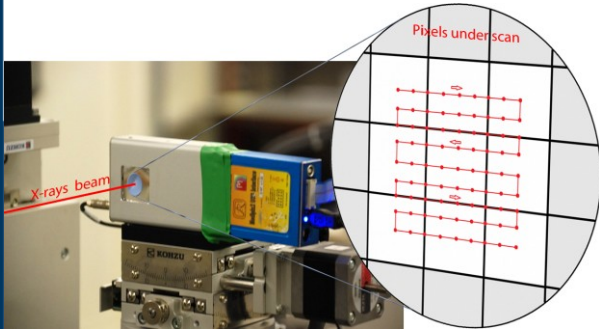
**Fluence:  $1 \times 10^{15}$  1 MeV  $n_{eq}$   $cm^{-2}$**

**Sr-90 measured  $\sim 100\%$  of  $Q_0$  collected**



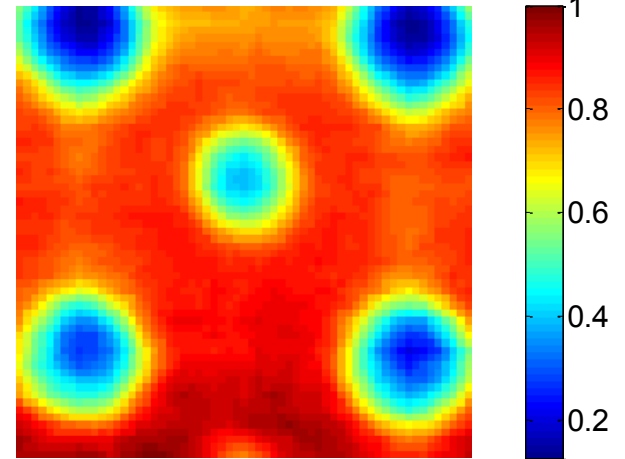
- Two p+ columns evident
- Non-uniform charge collection outside of column position
- Area of low charge collection between the n+ contacts where a low field is present
- Low field areas have greater probability of charge trapping

# X-ray test beam: Pixel Maps

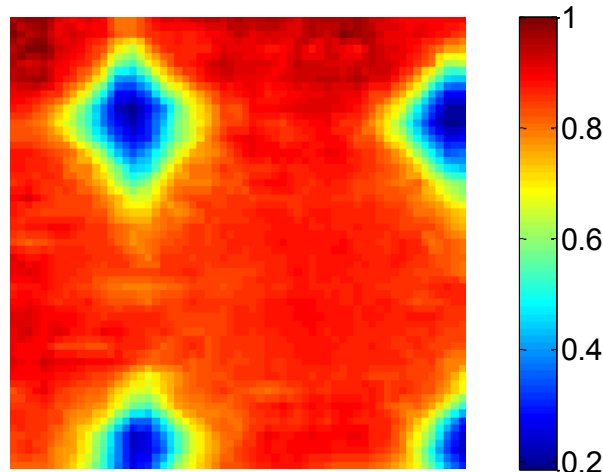


- **77.5 $\mu\text{m}$  square scans**
- **2.5 $\mu\text{m}$  steps**
- **Background subtracted**
- **Interpolated**

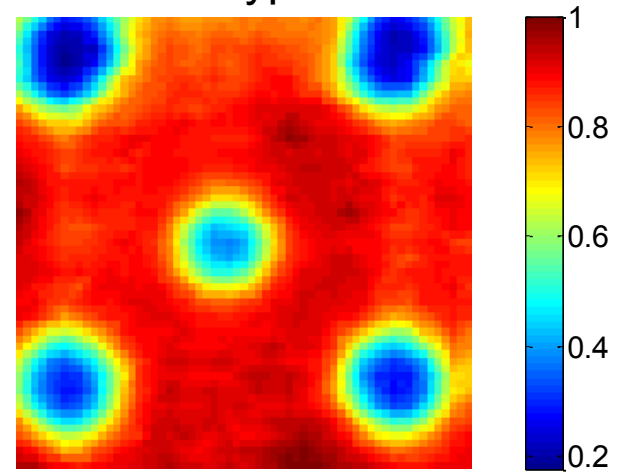
N-Type



Planar



P-Type

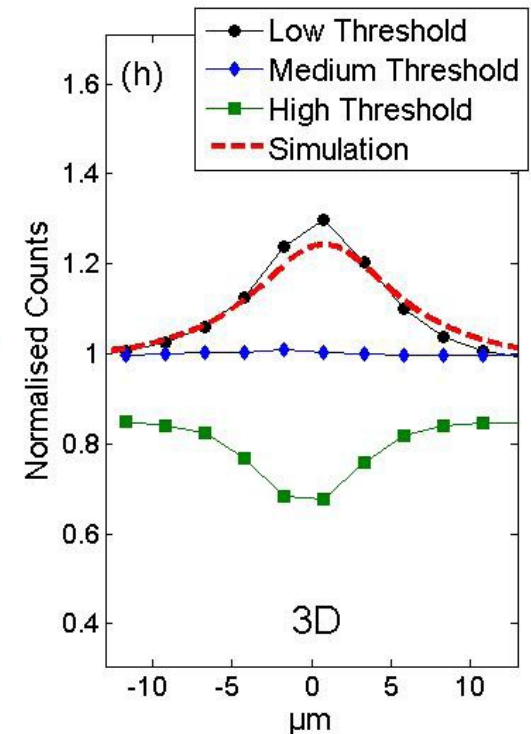
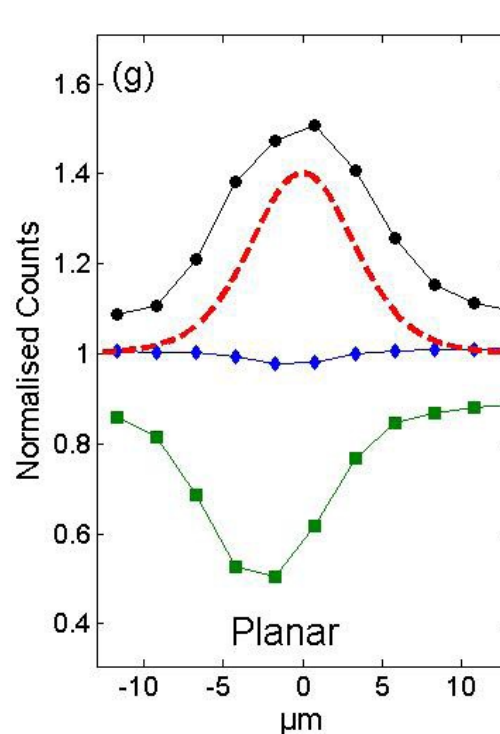
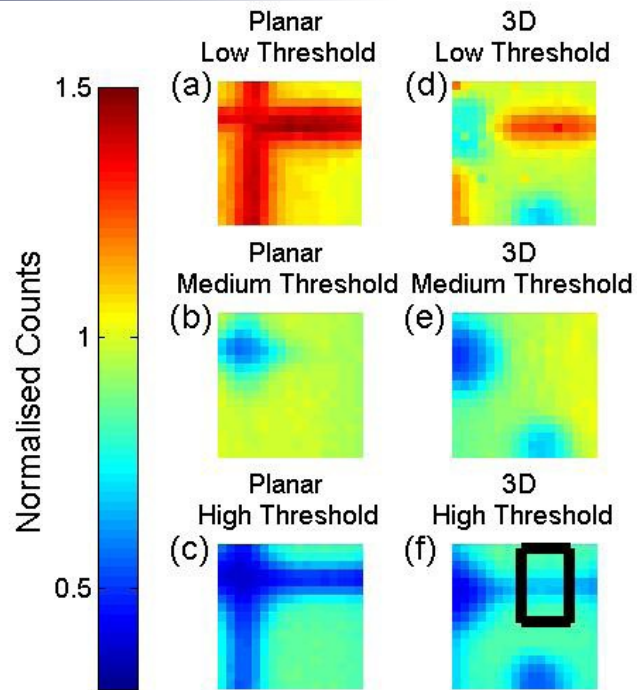


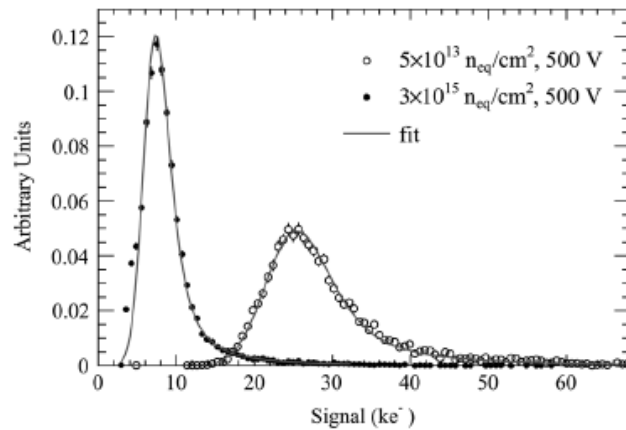
Physics	Model
Mobility	Doping dependence, High Electric field saturation
Generation and Recombination	Doping dependant Shockley-Read-Hall Generation recombination, Surface recombination model
Impact ionization	University of Bologna impact ionization model
Tunneling	Band-to-band tunneling, Hurkx trap-assisted tunneling
Oxide physics	Oxide as a wide band gap semiconductor for mips (irradiated), interface charge accumulation
Radiation model	Acceptor/Donor states in the band gap (traps)

## P-TYPE RADIATION DAMAGE MODEL

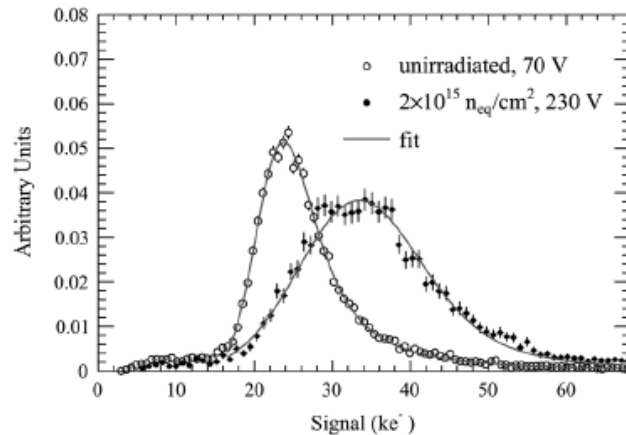
Defect's energy (eV)	Introduction rate ( $cm^{-1}$ )	Electron capture cross-section ( $cm^{-2}$ )	Hole capture cross-section ( $cm^{-2}$ )
$E_c - 0.42$	1.613	2.e-15	2e-14
$E_c - 0.46$	0.9	5e-15	5e-14
$E_c - 0.10$	100	2e-15	2.5e-15
$E_v + 0.36$	0.9	2.5e-14	2.5e-15





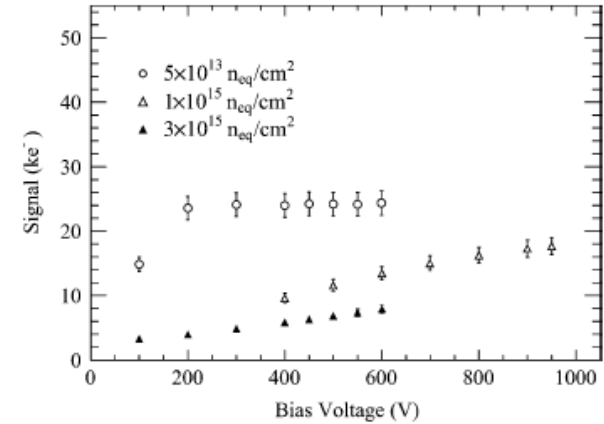


(a)

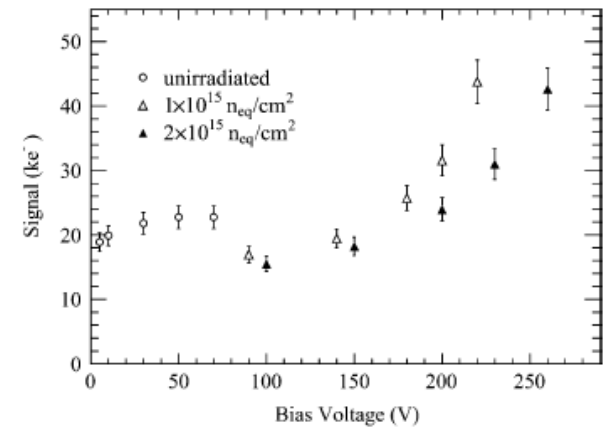


(b)

Fig. 2. Normalized signal distributions for different irradiation fluences (a) measured with planar detectors and (b) measured with 3D detectors. The fit superimposed is a convolution of a Landau function and a Gaussian.



(a)



(b)

Fig. 3. Signal as a function of the applied bias voltage for different irradiation fluences (a) measured with the planar sensors and (b) measured with the 3D sensors. The errors are dominated by a systematic contribution due to the calibration uncertainty.

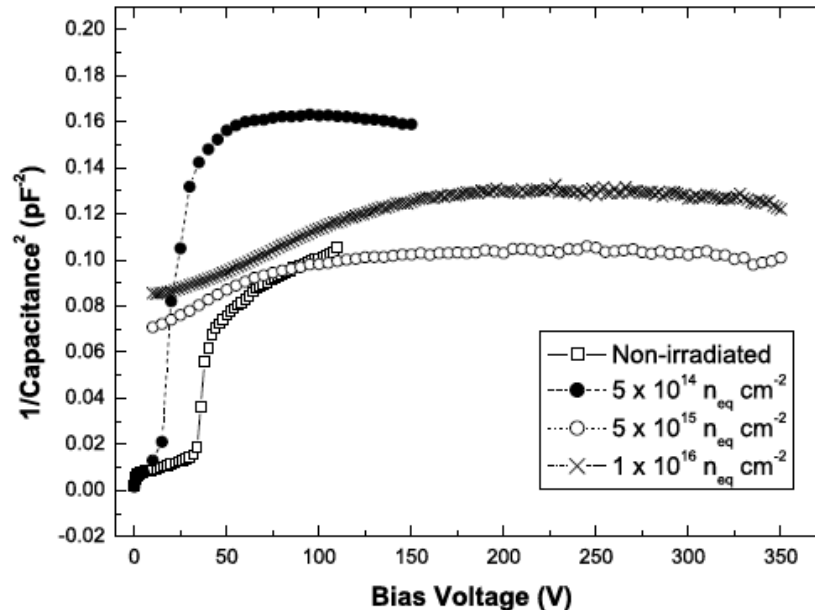


Fig. 6. Strip to back plane capacitance as a function of bias voltage measured after four different irradiation levels, namely; 0, 0.5, 5 and  $10 \times 10^{15} \text{ cm}^{-2}$  1 MeV  $n_{\text{eq}}$ . The four curves are labeled on the figure.